




Technical data

	InlineCoater™ 500	InlineCoater™ 300	InlineCoater™ 300-PECVD
Chamber size (mm)	L: 515 W: 315 H: 75 - 150 	L: 300 W: 180 H: 50 - 150 	L: 300 W: 180 H: 50 - 150 
Process chambers	3	3	3
Source orientation	Top, bottom, or both	Top, bottom, or both	<i>Not applicable</i>
Process options	Sputtering Reactive sputtering Cathodic arc evaporation HiPIMS PECVD Plasma etch Substrate bias <i>Other possible</i>	Sputtering Reactive sputtering Cathodic arc evaporation HiPIMS PECVD Plasma etch Substrate bias <i>Other possible</i>	PECVD Plasma etch
Load-lock	Yes	Yes	Yes
Cycle time, from	20 sec	15 sec	15 sec
System dimension (mm)	L:4600 W:1800 H:2400	L:3200 W:2600 H:2400	L:3200 W:1400 H:2400
	